

REMARKS

Claims 1, 3-10, and 12-20 remain active in this application. Claims 2 and 11 have been withdrawn from consideration as being substantially redundant over claim 7 following amendment, and claim 12, respectively. Claim 21 has been added. The specification has been reviewed and editorial revisions made where seen to be appropriate. Claims 1, 3-10, and 12-20 have been amended editorially. Claims 4, 10, and 17-20 have been amended to change claim dependency. Support for the amendments of the claims is found throughout the application, particularly in Figures 2 and 3 and the description thereof on page 4, lines 13-25; page 5, lines 1-12; page 6, lines 15+; and page 7, line 14 to page 8, line 19. The Examiner's indication of allowance of the drawings is noted with appreciation. No new matter has been introduced into the application.

The Examiner's rejection of claims 1-20 under 35 U.S.C. 103(a) in view of Shigaraki (Pub. No.: 2002/0006675 A1) and Miwa (Pub. No.: 2002/0071105 A1) are respectfully traversed as the references, individually or combined, do not teach the meritorious effects of the current invention.

Particularly in regard to independent claims 1 and 13, and subsequently regarding dependent claims 2-12, and 14-20, Shigaraki discloses a lithography system (para 0002, lines 1-5 and para 0076, lines 1-2), comprising a reticle chamber having a chamber opening (para 0042, lines 1-7 and 11 in Fig. 1B); a reticle chamber maintenance panel over which is mounted to the reticle chamber opening (para 0035, lines 3-6), and a reticle stage (para 0042, lines 1-6), and accessible through the reticle chamber opening (para 0038, lines

1-8 and Fig. 1B). However, all of Shigaraki's teachings are recognized as prior art (as viewed in Figure 1) by the current invention and do not begin to address the form or function of the current invention: to remove the reticle stage and adjoining reticle table from the reticle chamber in a single direction without requiring disassembly of either the projection optic or the illumination optic.

Further, with respect to dependent claims 6 and 19, Shigaraki discloses a lithography system comprising a projection optic system, an illuminator optic system, and a reticle table mounted to the reticle stage and positioned between the projection and illuminator optic systems (para 0041, lines 13-14; para 0036, lines 1-6; para 0042, lines 3-8, and 2, 4, and 5 in Fig. 1A). Shigaraki further includes a body structure, which is mounted to a lower portion of the chamber, the projection optic and the illuminator optic being mounted to the body structure during the removal of the reticle table and the stage (11b, 11c, 11e, and 14 in Fig. 1A). These teachings of Shigaraki are also recognized as prior art (as viewed in Figure 1) by the current invention and do not begin to address the invention's aforementioned meritorious effects.

The additional reference, Miwa, explicitly or implicitly applied to claims 1-20, does not answer the deficiencies of Shigaraki in order to support a *prima facie* demonstration of obviousness. More specifically, the Examiner asserts that Miwa discloses a maintenance panel which is removably mounted to the reticle chamber opening (para 0034, lines 6-14 and 12 in Fig. 1), wherein the chamber opening provides access to the reticle stage (11 and 12 in Fig. 1). It is respectfully submitted, however, that Miwa makes no reference to a reticle stage in any citation provided

by the Examiner within the drawings or text. Rather, the intention of Miwa is to allow automated extraction of the reticles (para 0034, line 5) not access and/or removal of the reticle stage. Additionally, the process for extracting the reticles claimed in Miwa requires a multiaxial transfer robot (para 0034, line 8 and 9 in Fig. 1) because successful removal of the reticle requires multi-directional movement; a task specifically avoided by the present invention and not the removal of the reticle stage in a single direction.

Further, Miwa requires the multiaxial transfer robot to perform the task of reticle removal, whereas the current invention is designed such that a human can access the reticle stage for removal, replacement, or other maintenance. Thus, the size and cost of the invention is reduced without requiring such additional unnecessary components. Further still, neither Shigaraki nor Miwa propose an angled access facility.

As these references in combination fail to describe either the intended purpose, function, or embodiment of the current invention, a *prima facie* demonstration has not been made and the Examiner's rejections of claims 1-20 are respectfully traversed.

Since all rejections, objections and requirements contained in the outstanding official action have been fully answered and shown to be in error and/or inapplicable to the present claims, it is respectfully submitted that reconsideration is now in order under the provisions of 37 C.F.R. §1.111(b) and such reconsideration is respectfully requested. Upon reconsideration, it is also respectfully submitted that this application is in condition for allowance and such action is therefore respectfully requested.

A petition for a two month extension of time is filed concurrently herewith. If any further extension of time is required for this response to be considered as being timely filed, a conditional petition is hereby made for such extension of time. Please charge any deficiencies in fees and credit any overpayment of fees to Attorney's Deposit Account No. 50-2041.

Respectfully submitted,



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